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CLAIMS

1. A method of patterning a functional material onto a substrate, comprising the steps of (a) applying a layer of protective material, soluble in a solvent in which the functional material is insoluble, to at least one major surface of said substrate; (b) removing areas of said layer to gain access to the substrate in well-defined regions; (c) depositing the functional material at least onto the substrate in the well-defined regions; and (d) removing the remaining layer of protective material from the substrate by dissolution in said solvent.

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- 2. The method of claim 1, wherein said substrate comprises glass.
- 3. The method of claim 1, wherein said substrate comprises silicon.
- 15 4. The method of claim 1, wherein said substrate comprises plastics material.
 - 5. The method of any preceding claim, wherein said substrate comprises a charge injection layer.
- 20 6. The method of any preceding claim, wherein said protective material comprises organic material.
 - 7. The method of claim 6, wherein said layer of protective material comprises a water soluble polymer selected from poly(vinyl alcohol), polymethyl ether, polymethylacrylamide, doped polythiophene, polyethylene glycol and doped polyaniline.
 - 8. The method of claim 6, wherein said layer of protective material comprises an alcohol soluble polymer.

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9. The method of any preceding claim, wherein said protective material comprises inorganic material.

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- 10. The method of claim 9, wherein said protective material is selected from silicon, silicon nitride and silicon oxide.
- The method of any preceding claim, wherein a layer of a second protective material is applied subsequent to step (a), is removed in the well-defined regions in step (b) and is subsequently removed other than in the well-defined regions.
- 10 12. The method of claim 11, wherein said layer of second protective material comprises an inorganic layer.
 - 13. The method of claim 12, wherein said layer of second protective material is selected from silicon, silicon nitride and silicon oxide.

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- 14. The method of claim 11, wherein said layer of second protective material comprises a metal layer.
- The method of claim 14, wherein said layer of second protective material is selected from nickel, aluminum and chromium.
 - 16. The method of any preceding claim, wherein in step (b) said protective material is removed from the well-defined regions by laser ablation.
- 25 17. The method of any preceding claim, wherein in step (b) said protective material is removed from the well-defined regions using a lift off process.
- 18. The method of any one of claims 11 to 15, wherein in step (b) said layer of second protective material is removed from the well-defined regions using a first process to expose said areas of said protective material and wherein said areas of said protective material are removed using a second process to gain access to the substrate.

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- 19. The method of claim 18, wherein said first process comprises laser ablation.
- 20. The method of claim 18, wherein said first process comprises a stamping or puncturing process.
- 21. The method of claim 18, wherein said first process comprises a photolithography step to define and expose said layer of second protective material in the well-defined regions and said second process comprises an etching step to remove said second protective material in the well-defined regions.
- The method of any preceding claim, wherein in step (c) the functional material is deposited by a method selected from spin coating, evaporation, and sputtering.
 - 23. The method of any preceding claim, wherein after step (c) an additional layer of protective material is applied over the functional material, said additional layer being removed in step (d).
- 24. The method of claim 23, wherein said additional layer comprises the same protective material, soluble in a solvent in which the functional material is insoluble.
- 25 25. The method of any preceding claim, wherein said functional material comprises an organic electro-optically active material.
 - 26. The method of any one of claims 1 to 24, wherein said functional material comprises a biochemical or biological reagent.

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- 27. The method of any preceding claim, comprising further steps of patterning a further functional material to the substrate, the further steps comprising repeating steps (a) to (d) for the further functional material.
- The method of any one of claims 1 to 26, comprising the steps of after step (c), applying an additional layer of protective material; removing areas of said additional layer to gain access to the substrate in additional well-defined regions; and depositing an additional functional material at least onto the substrate in the additional well-defined regions.

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29. A device comprising a substrate bearing patterned electroluminescent material, the substrate and electroluminescent material being covered by first and/or second layers of protective material, said layers having apertures giving access to well-defined regions of the substrate.

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- 30. An optoelectronic device comprising a substrate and a plurality of sub-pixels comprising polymer light emitting diodes arrange to emit light of different colors, the spacing between said sub-pixels being less than 15 μm.
- 20 31. An optoelectronic device according to claim 30, wherein said spacing is less than 10 μm .
 - 32. An optoelectronic device according to claim 31, wherein said spacing is less than 5 μ m.

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33. An optoelectronic device according to claim 30, 31 or 32, comprising a quarter video graphic array (QVGA) device.